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			POIRE		APPLICANT							
LIST	OF	REFERENCES	LICANT	<u>(</u> 2)	Kazunari HO	NMA, et al	l					
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	Al	11-080181	March 26, 1999	Japan							×	
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		OTHER REF	ERENCES (Includia	ng Author, Title,	Da	te, Pertinent	Pages, Et	c.)				
		Item I "Low Tem	perature Deposition	n Material"								
	AM	Section 4 "New Deposition Material" Ferroelectric Memory Advanced Process										
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.